

L Number	Hits	Search Text	DB	Time stamp
-	3182	(magnetic adj head).ti.	USPAT; US-PGPUB	2003/01/09 10:11
-	710	(thin adj film adj magnetic adj head).ti.	USPAT; US-PGPUB	2002/12/26 10:47
-	71	((thin adj film adj magnetic adj head).ti.) and pole adj width	USPAT; US-PGPUB	2003/01/02 10:31
-	551	(thin adj film adj magnetic adj head).ti. and coil and record\$3	USPAT; US-PGPUB	2002/12/26 10:48
-	396	(thin adj film adj magnetic adj head).ti. and coil and pole and record\$3	USPAT; US-PGPUB	2002/12/26 10:48
-	85	(magnetic adj head).ti. and ((ion adj beam) same angle)	USPAT; US-PGPUB	2003/01/02 10:03
-	201	(magnetic adj head) and RIE and pole and mask	USPAT; US-PGPUB	2003/01/06 16:36
-	567	(magnetic adj head) and ion and (milling or reactive) and pole and mask	USPAT; US-PGPUB	2003/01/06 16:37
-	312	(magnetic adj head) and ion and (milling or reactive) and pole and mask and etch\$3 and angle	USPAT; US-PGPUB	2003/01/02 10:18
-	289	(magnetic adj head) and (reactive adj ion) and pole and mask and etch\$3	USPAT; US-PGPUB	2003/01/06 16:28
-	267	(magnetic adj head) and (ion adj milling) and pole and mask and etch\$3 and angle	USPAT; US-PGPUB	2003/01/06 16:30
-	1071	(360/126).CCLS.	USPAT; US-PGPUB	2003/01/02 10:32
-	263	(magnetic adj head).ti. and etch\$3.clm.	USPAT; US-PGPUB	2003/01/03 11:49
-	97	(magnetic adj head).ti. and (mask and etch\$3).clm.	USPAT; US-PGPUB	2003/01/09 14:30
-	5	(magnetic adj head).ti. and (mask and (first adj etch\$3)).clm.	USPAT; US-PGPUB	2003/01/06 10:08
-	5	(magnetic adj head).ti. and (mask and (second adj etch\$3)).clm.	USPAT; US-PGPUB	2003/01/06 10:09
-	72	((ion adj (milling or beam)) and mask and etch\$3 and angle).clm.	USPAT; US-PGPUB	2003/01/06 10:14
-	17	((ion adj (milling or beam)) and mask and magnetic and etch\$3 and angle).clm.	USPAT; US-PGPUB	2003/01/06 10:35
-	9	((reactive adj ion) and mask and magnetic and etch\$3 and angle).clm.	USPAT; US-PGPUB	2003/01/06 10:38
-	100	((reactive adj ion) and mask and magnetic and etch\$3).clm.	USPAT; US-PGPUB	2003/01/06 10:37
-	11	(magnetic adj head) and (reactive adj ion) and pole and mask and etch\$3	JPO; DERWENT	2003/01/06 16:33
-	95	(magnetic adj head) and (reactive adj ion)	JPO; DERWENT	2003/01/06 16:29
-	44	(magnetic adj head) and (ion adj milling) and angle	JPO; DERWENT	2003/01/06 16:31
-	1602	(magnetic adj head) and etch\$3	JPO	2003/01/06 16:34
-	2	(magnetic adj head) and RIE and pole and mask	DERWENT	2003/01/06 16:36
-	161	(magnetic adj head) and ion and (milling or reactive)	DERWENT	2003/01/14 09:22
-	423	(magnetic adj head) and etch\$3 and ion and mask and pole	USPAT	2003/01/09 12:12
-	16	(magnetic adj head) and etch\$3 and ion and mask and pole	DERWENT	2003/01/09 08:29
-	62	(manufacturing adj thin adj film adj magnetic adj head).ti.	USPAT; US-PGPUB	2003/01/09 10:13
-	33	mask same photoresist same (metal or nickel or copper)adj film and magnetic adj head	USPAT; US-PGPUB	2003/01/09 10:28
-	32	(magnetic adj head) and etch\$3 and ion and mask and pole and photoresist and metal adj film	USPAT	2003/01/09 12:13
-	95	(magnetic adj head) and (iron same cobalt same zirconium)	USPAT; US-PGPUB	2003/01/13 13:12
-	4	(magnetic adj head) and polish same CMP same magnetic adj layer	USPAT; US-PGPUB	2003/01/13 14:19

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-	4	(magnetic adj head) and etch\$3 and ion and narrow and pole	JPO	2003/01/13 13:45
-	5	polish same CMP same magnetic adj layer	USPAT; US-PGPUB	2003/01/13 14:20
-	0	(magnetic adj head) and ion and (milling or reactive) and iron adj nitride	DERWENT	2003/01/14 09:22
-	30	(magnetic adj head) and iron adj nitride	DERWENT	2003/01/14 09:23
-	58	(magnetic adj head) and ion and etch\$3 and mask and iron adj nitride	USPAT; US-PGPUB	2003/01/14 09:27
-	234	(magnetic adj head) and magnetic same FeN	USPAT; US-PGPUB	2003/01/14 09:28